

Access DB# 96219

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Thomas Ray DVC Examiner #: 6933e Date: 6/9/03
Art Unit: 1711 Phone Number 303-237 Serial Number: 10176172
Mail Box and Bldg/Room Location: 3/4029 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc., if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: _____

Inventors (please provide full names): _____

Earliest Priority Filing Date: _____

For Sequence Searches Only Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

*Either one of Formulae (3) (4) or (5) with Formula (2).
Thanks*

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Searcher: ED

Type of Search

Vendors and cost where applicable

NA Sequence (#) STN \$ 560.63

AA Sequence (#) Dialog

Structure (#) ✓ (2) Questel/Orbit

Bibliographic ✓ (2) Link

Litigation ✓ (2) Lexis/Nexis

Faxtext Sequence Systems

Patent Family WWW/Internet

Other Other (specify)

Truong 10/070,152

Page 1

=> file reg
FILE 'REGISTRY' ENTERED AT 13:53:43 ON 10 JUN 2003
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FILE 'LREGISTRY' ENTERED AT 10:02:54 ON 10 JUN 2003
L12 STR

FILE 'REGISTRY' ENTERED AT 10:07:26 ON 10 JUN 2003
L13 50 S L12
L14 STR L12
L15 50 S L14
L16 16749 S L14 FUL
SAV TEM L16 TRU152/A

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L17 STR

FILE 'REGISTRY' ENTERED AT 12:42:18 ON 10 JUN 2003
L18 SCR 2043
L19 50 S L17
E 4-BROMO-1,8-NAPHTHALIC ANHYDRIDE/CN
L20 1 S E3
E "HEXAMETHYLENE-1,6-BIS(DICYANDIAMIDE)" /CN
E HEXAMETHYLEDIAMIINE/CN
L21 1 S E3
L22 7 S 81-86-7/CRN
L23 7447 S 124-09-4/CRN
L24 1 S L22 AND L23

FILE 'HCAPLUS' ENTERED AT 12:48:35 ON 10 JUN 2003
L25 1 S L24

FILE 'LREGISTRY' ENTERED AT 12:50:16 ON 10 JUN 2003
L26 0 S L17 AND L18

FILE 'REGISTRY' ENTERED AT 12:55:22 ON 10 JUN 2003
L27 50 S L17 AND L18
L28 2659 S L17 AND L18 FUL
SAV L28 TRU152A/A
L29 2 S L28 AND L16

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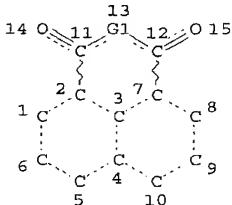
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Page 2

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L35 0 S L34 AND L31
L36 2 S L25 OR L30 OR L33

FILE 'REGISTRY' ENTERED AT 13:53:43 ON 10 JUN 2003

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L14 STR



VAR G1=N/O
NODE ATTRIBUTES:
DEFAULT MLEVEL IS ATOM
DEFAULT ELEVEL IS LIMITED

GRAPH ATTRIBUTES:
RSPEC I
NUMBER OF NODES IS 15

STEREO ATTRIBUTES: NONE
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SEARCH TIME: 00.00.01

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GRAPH ATTRIBUTES:
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 NUMBER OF NODES IS 7

STEREO ATTRIBUTES: NONE
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100.0% PROCESSED 2682 ITERATIONS 2659 ANSWERS
 SEARCH TIME: 00.00.01

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 FILE 'HCAPLUS' ENTERED AT 13:54:29 ON 10 JUN 2003
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=> d 136 1-2 cbib abs hitstr hitind

L36 ANSWER 1 OF 2 HCAPLUS COPYRIGHT 2003 ACS
 2001:185503 Document No. 134:218307 Antimicrobial polymers containing
 chromophoric markers.. Collins, Andrew Neale; Bothwell, Brian
 David; Mcpherson, Graham John (Avecia Ltd., UK). PCT Int. Appl. WO
 2001017356 A1 20010315, 35 pp. DESIGNATED STATES: W: AE, AG, AL,
 AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CR, CU, CZ, DE,
 DK, DM, DZ, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS,
 JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK,
 MN, MW, MX, MZ, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ,
 TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW, AM, AZ, BY, KG, KZ,
 MD, RU, TJ, TM; RW: AT, BE, BF, BJ, CF, CG, CH, CI, CM, CY, DE, DK,
 ES, FI, FR, GA, GB, GR, IE, IT, LU, MC, ML, MR, NE, NL, PT, SE, SN,
 TD, TG. (English). CODEN: PIXXD2. APPLICATION: WO 2000-GB2864
 20000725. PRIORITY: GB 1999-20774 19990903.

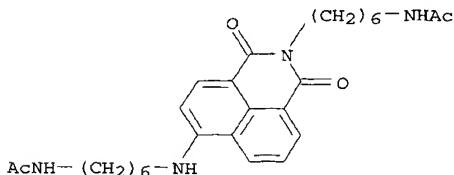
AB An antimicrobial polymer is given, which carries a covalently-bound
 chromophoric marker. The antimicrobial polymer is preferably a
 cationic antimicrobial polymer, esp. a poly(hexamethylenebiguanide).
 Also claimed are compns. contg. the antimicrobial polymer, a method
 for treating a medium using the antimicrobial polymer and a method
 for detecting the antimicrobial polymer in a medium. The prepn. of
 chromophoric markers, such as N-(-aminohexyl)-4-(6-aminohexyamino)-
 1,8-naphthalimide, is given.

IT 329710-62-5P
 (intermediate in prepn. of chromophoric marker for antimicrobial
 polymers)

RN 329710-62-5 HCAPLUS

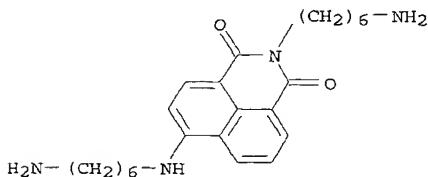
CN Acetamide, N-[6-[6-[(6-(acetylamino)hexyl)amino]-1,3-dioxo-1H-

benz[de]isoquinolin-2(3H)-yl]hexyl - (9CI) (CA INDEX NAME)

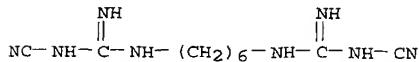


- IT 329710-65-8P 329710-66-9DP, reaction product with chromophoric markers
(prepn. as antimicrobial polymer contg. chromophoric markers.)
- RN 329710-65-8 HCAPLUS
- CN Guanidine, N,N'-(1,6-hexanediylyl)bis[N'-cyano-, polymer with 2-(6-aminohexyl)-6-[(6-aminohexyl)aminol]-1H-benz[de]isoquinoline-1,3(2H)-dione and 1,6-hexanediamine dihydrochloride (9CI) (CA INDEX NAME)

CM 1

CRN 329710-61-4
CMF C₂₄ H₃₄ N₄ O₂

CM 2

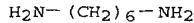
CRN 15894-70-9
CMF C₁₀ H₁₈ N₈

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Page 5

CM 3

CRN 6055-52-3
CMF C6 H16 N2 . 2 Cl H

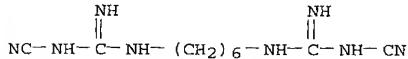


2 HCl

RN 329710-66-9 HCAPLUS
CN Guanidine, N,N'-(1,6-hexanediyil)bis[N'-cyano-, polymer with
6-bromo-1H,3H-naphtho[1,8-cd]pyran-1,3-dione and 1,6-hexanediamine
dihydrochloride (9CI) (CA INDEX NAME)

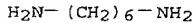
CM 1

CRN 15894-70-9
CMF C10 H18 N8



CM 2

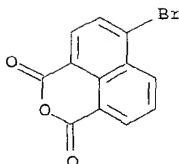
CRN 6055-52-3
CMF C6 H16 N2 . 2 Cl H



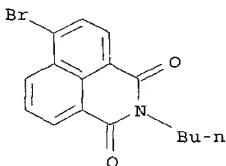
● 2 HCl

CM 3

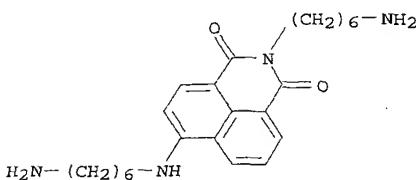
CRN 81-86-7
CMF C12 H5 Br O3



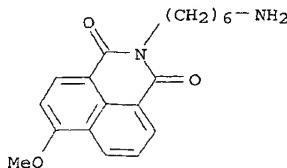
IT 92874-17-4P 329710-61-4P 329710-63-6DP,
Wang resin deriv.
(prepn. as chromophoric marker for antimicrobial polymers)
RN 92874-17-4 HCAPLUS
CN 1H-Benz[de]isoquinoline-1,3(2H)-dione, 6-bromo-2-butyl- (9CI) (CA INDEX NAME)



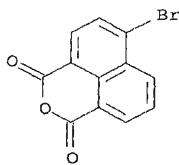
RN 329710-61-4 HCAPLUS
CN 1H-Benz[de]isoquinoline-1,3(2H)-dione, 2-(6-aminohexyl)-6-[(6-aminohexyl)amino]- (9CI) (CA INDEX NAME)



RN 329710-63-6 HCAPLUS
CN 1H-Benz[de]isoquinoline-1,3(2H)-dione, 2-(6-aminohexyl)-6-methoxy- (9CI) (CA INDEX NAME)



IT 81-86-7, 4-Bromo-1,8-naphthalic anhydride
(reactant in prepn. of chromophoric marker for antimicrobial polymers)
RN 81-86-7 HCAPLUS
CN 1H,3H-Naphtho[1,8-cd]pyran-1,3-dione, 6-bromo- (9CI) (CA INDEX NAME)



IC ICM A01N047-44
ICS A01N033-12; C09B057-00
CC 5-2 (Agrochemical Bioregulators)
Section cross-reference(s): 38, 41
IT 49631-88-1P 329710-62-5P
(intermediate in prepn. of chromophoric marker for antimicrobial polymers)
IT 329710-65-8P 329710-66-9DP, reaction product with chromophoric markers
(prepn. as antimicrobial polymer contg. chromophoric markers.)
IT 92874-17-4P 329710-61-4P 329710-63-6DP,
Wang resin deriv. 329710-64-7DP, Wang resin deriv.
329748-60-9DP, Wang resin deriv.
(prepn. as chromophoric marker for antimicrobial polymers)
IT 81-86-7, 4-Bromo-1,8-naphthalic anhydride 124-09-4,
Hexamethylenediamine, reactions
(reactant in prepn. of chromophoric marker for antimicrobial polymers)

L36 ANSWER 2 OF 2 HCAPLUS COPYRIGHT 2003 ACS
2000:694433 Document No. 133:267982 UV-absorbing thermosetting resin compositions, prepregs, laminates, and printed circuit boards.

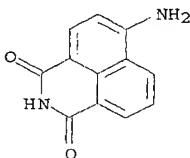
Takata, Kosuke; Murai, Akira; Oze, Masahisa (Hitachi Chemical Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2000273314 A2 20001003, 4 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1999-78681 19990323.

AB The compns. contain 4-aminonaphthalimide (I) N,N'-dialkyl derivs. and 4-methyl-7-(diethylamino)coumarin (II). Thus, brominated epoxy resin (YDB 400) 100, dicyandiamide 3, 2-ethyl-4-methylimidazole 0.17, I deriv. (Neosuper HR 60) 0.1, and II (Neosuper HR 1) 0.3 part were dissolved in ethylene glycol mono-Me ether and DMF to give a varnish, which was impregnated into a glass cloth, dried, sandwiched with Cu foils, and hot-pressed to give a Cu-clad laminate. Simultaneous exposure was carried out in resist pattern formation on both sides of a double-sided printed circuit board prep'd. from the laminate.

IT 1742-95-6D, 4-Aminonaphthalimide, derivs.
(UV absorber; UV-absorbing thermosetting resin compns. for manuf. of double-sided printed circuit boards for simultaneous exposure on both sides in resist pattern formation)

RN 1742-95-6 HCPLUS

CN 1H-Benz[de]isoquinoline-1,3(2H)-dione, 6-amino- (9CI) (CA INDEX NAME)



IT 134096-54-1P
(UV-absorbing thermosetting resin compns. for manuf. of double-sided printed circuit boards for simultaneous exposure on both sides in resist pattern formation)

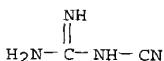
RN 134096-54-1 HCPLUS

CN Guanidine, cyano-, polymer with (chloromethyl)oxirane and 4,4'-(1-methylethylidene)bis[2,6-dibromophenol] (9CI) (CA INDEX NAME)

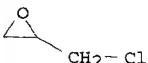
CM 1

CRN 461-58-5

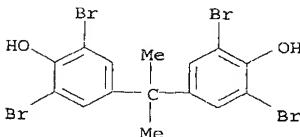
CMF C2 H4 N4



CM 2

CRN 106-89-8
CMF C3 H5 Cl O

CM 3

CRN 79-94-7
CMF C₁₅ H₁₂ Br₄ O₂

IC ICM C08L101-00
ICS B32B015-08; C08J005-24; C08K005-1545; C08K005-3432; C08L063-00;
H05K001-03

CC 38-3 (Plastics Fabrication and Uses)
Section cross-reference(s) : 76

IT 1742-95-6D, 4-Aminonaphthalimide, derivs. 298211-33-3,
Neo-Super HR 60

(UV absorber; UV-absorbing thermosetting resin compns. for manuf. of double-sided printed circuit boards for simultaneous exposure on both sides in resist pattern formation)

IT 134096-54-1P

(UV-absorbing thermosetting resin compns. for manuf. of double-sided printed circuit boards for simultaneous exposure on both sides in resist pattern formation)